

2-Nitro- and 2,4-Dinitrobenzenesulfonamides as Protecting Groups for Primary Amines

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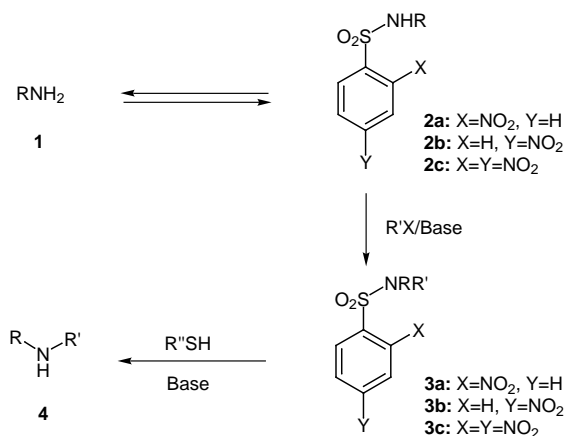
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Abstract: Procedures for the deprotection of the 2-nitro- and 2,4-dinitrobenzenesulfonamides to give the corresponding primary amines were developed. The 2-Nitrobenzenesulfonyl group was effectively removed by HSCH₂CH₂OH/DBU or PhSH/Cs₂CO₃ in DMF under mild conditions to give the corresponding primary amines in high to excellent yield. For removal of the 2,4-dinitrobenzenesulfonyl group, the use of thiol alone (HSCH₂CH₂OH or PhSH) was quite effective. Selective deprotection of 2,4-dinitrobenzenesulfonamide in the presence of 2-nitrobenzenesulfonamide has also been achieved.

Key words: 2-nitrobenzenesulfonamide, 2,4-dinitrobenzenesulfonamide, protecting groups, deprotection, primary amines

2- and 4-Nitrobenzenesulfonamides, **2a** and **2b**, are unique among the amino protective groups. They are readily prepared from primary amines **1**, then easily *N*-alkylated to give *N,N*-disubstituted sulfonamides **3a,b**, with subsequent removal of the arylsulfonyl groups to afford secondary amines **4**. Accordingly, since introduced by Fukuyama et al.,¹ these protecting/activating groups have been widely used for the preparation of secondary amines both in solution- and solid-phase syntheses.^{2,3} 2,4-Dinitrobenzenesulfonamides **3c** can be utilized in the same manner and, in addition, it is selectively deprotected in the presence of 2-nitrobenzenesulfonamides **3a**, leading to a wide variety of diamines with the combined use of these groups.⁴ Direct transformation of **2c** to amides, ureas, thioamides, and thioureas through a deprotection/functionalization sequence has also been reported.⁵ However, simple deprotection of **2** to reproduce the corresponding primary amines **1** has not been fully investigated; thus, deprotection of 2-nitrobenzenesulfonamide **2a** resulted in low yield⁶ or should be carried out indirectly through further protection with urethane groups.⁷ Only a few such successful results have been reported.⁸ In fact, we have encountered difficulty during our studies on the synthesis of acylpolyamine spider toxins, which prompted us to investigate the deprotection of **2** to **1**. We report herein the procedures for the deprotection of 2-nitro- and 2,4-dinitrobenzenesulfonamides, **2a** and **2c**, to directly give the corresponding primary amines **1**. Selective deprotection of 2,4-dinitrobenzenesulfonamide in the presence of 2-nitrobenzenesulfonamide on diamine is also described.



Scheme 1

A variety of conditions for removing the 2-nitrobenzenesulfonyl (Ns) group from 2-nitrobenzenesulfonamide **2a** were examined using 4-methoxybenzylamine as a model substrate (Entry 1 in Table 1). Consequently, we found that the use of HSCH₂CH₂OH/DBU (Method A) and PhSH/Cs₂CO₃ (Method B) in DMF were the most effective, giving the primary amine in 86% and 88% yield, respectively, at 0 °C–room temperature for 30 min. Table 1 summarizes the results of a variety of substrates. In Method A, DBU can be replaced by Cs₂CO₃ and, in Method B, Cs₂CO₃ can be replaced by DBU; thus, any combination of HSCH₂CH₂OH or PhSH as a thiol with DBU or Cs₂CO₃ as a base may essentially give the same results. Furthermore, when using PhSH/DBU, acetonitrile (MeCN) can be used as the solvent instead of DMF. Under the conditions of Methods A and B, no racemization took place when applied to the optically active α -branched amines (Entries 3 and 4). Fukuyama's standard procedures using PhSH/K₂CO₃/DMF and HSCH₂CO₂H/LiOH for secondary sulfonamides were sluggish and did not go to completion. The conditions similar to Method A have been successfully used for the deprotection of secondary 2-nitrobenzenesulfonamides in the solid-phase.^{2c,h} Accordingly, the conditions employing HSCH₂CH₂OH/DBU/DMF may be the most widely used and the method of choice for any situation, primary or secondary sulfonamide and solution- or solid-phase synthesis.

Table 1 Deprotection of the 2-nitrobenzenesulfonamides

Entry	Sulfonamide	Method A ^a (% isolated yield)	Method B ^b (% isolated yield)
1		86	88
2		95	96
3		87 ^c	91 ^c
4		91 ^{c,d}	81 ^{c,d}
5		85 ^d	86 ^d

^a HSCH₂CH₂OH (2.0 eq), DBU (1.5 eq), DMF, 0 °C - rt, 30 min.

^b PhSH (2.0 eq), Cs₂CO₃ (1.2 eq), DMF, 0 °C - rt, 30 min.

^c The enantiopurity was confirmed by ¹H NMR analysis of its MTPA amide.

^d Isolated as the HCl salt.

For removal of the 2,4-dinitrobenzenesulfonyl (DNs) group from **2c**, the use of the thiol alone (HSCH₂CH₂OH or PhSH) was quite effective. Table 1 summarizes the results of a variety of 2,4-dinitrobenzenesulfonamides. The reaction smoothly proceeded with 2 equiv of HSCH₂CH₂OH (Method C) or PhSH (Method D) in DMF and went to completion within 1 h or 15 min, respectively, with excellent yields. For Method C, no other solvent is compatible, but various solvents (CH₂Cl₂, THF, MeCN and MeOH) can be used as well as DMF for Method D. Under these conditions, no racemization occurred as shown in Entries 3 and 4. In all cases, Fukuyama's original procedures for the secondary sulfonamides using *n*-PrNH₂ or HSCH₂CO₂H/Et₃N gave only a poor yield or a complex mixture. Employing *i*-PrNH₂ or NH₃ aq. instead of *n*-PrNH₂ did not improve the results, nor any conditions with the combined use of thiol (HSCH₂CO₂H, HSCH₂CH₂OH, PhSH) and base (NaHCO₃, pyridine, Et₃N, imidazole). Consequently, the procedures for deprotecting primary 2,4-dinitrobenzenesulfonamides are distinct from those of secondary 2,4-dinitrobenzenesulfonamides.

For the secondary sulfonamides, the DNs group is preferentially removed in the presence of the Ns group as Fukuyama et al. reported.^{4a} A similar transformation was realized for the primary sulfonamides as well. When the disulfonamide **5**, prepared from mono-nosylated putrescine **6th** in high yield, was subjected to the conditions for deprotecting the DNs group (Methods C and D), the primary amine **5** was obtained in 97% and 92% yields,

Table 2 Deprotection of the 2,4-dinitrobenzenesulfonamides

Entry	Sulfonamide	Method C ^a (% isolated yield)	Method D ^b (% isolated yield)
1		98	91
2		92	94
3		85 ^c	83 ^c
4		88 ^{c,d}	96 ^{c,d}
5		83 ^d	98 ^d

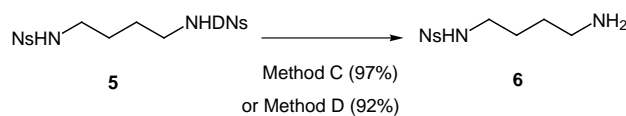
^a HSCH₂CH₂OH (2.0 eq), DMF, rt, 1 h.

^b PhSH (2.0 eq), DMF, rt, 15 min.

^c The enantiopurity was confirmed by ¹H NMR analysis of its MTPA amide.

^d Isolated as the HCl salt.

respectively, without affecting the Ns group at all (Scheme 2).

**Scheme 2**

In this study, we found the conditions for the deprotection of the 2-nitro- and 2,4-dinitrobenzenesulfonamides to reproduce primary amines, demonstrating that these groups are useful protective groups for primary amines as well as secondary amines and, therefore, the scope of these protective groups will become much wider and more useful. Moreover, the 2,4-dinitrobenzenesulfonyl group is preferentially deprotected in the presence of the 2-nitrobenzenesulfonyl group, which would also be useful for the synthesis of a variety of polyamine compounds.

Representative experimental procedures

Method A: To a stirred solution of *N*-(4-methoxybenzyl)-2-nitrobenzenesulfonamide (258 mg, 0.80 mmol) in DMF (3 mL), HSCH₂CH₂OH (125 mg, 1.60 mmol, 2 equiv) and DBU (182 mg, 1.20 mmol, 1.5 equiv) were slowly added at 0 °C. After stirring 30 min at room temperature, the reaction mixture was directly chromatographed on silica gel (8% MeOH-CHCl₃ and then 1: 3: 36 *i*-PrNH₂-MeOH-CHCl₃) to give 4-methoxybenzylamine (94 mg, 86%) as a colorless oil.

Method B: To a stirred solution *N*-(4-methoxybenzyl)-2-nitrobenzenesulfonamide (258 mg, 0.80 mmol) in DMF (3 mL), PhSH (176 mg, 1.60 mmol, 2 equiv) and Cs₂CO₃ (313 mg, 0.96 mmol, 1.2 equiv) were slowly added at 0 °C. After stirring for 0.5 h at room temperature, the reaction mixture was directly chromatographed on silica gel (8% MeOH-CHCl₃ and then 1: 3: 36 *i*-PrNH₂-MeOH-CHCl₃) to give 4-methoxybenzylamine (96 mg, 88%) as a colorless oil.

Method C: To a stirred solution of *N*-(4-methoxybenzyl)-2,4-dinitrobenzenesulfonamide (294 mg, 0.80 mmol) in DMF (2 mL), HSCH₂CH₂OH (125 mg, 1.60 mmol, 2 equiv) was added. After stirring 1 h at room temperature, the reaction mixture was directly chromatographed on silica gel (8% MeOH-CHCl₃ and then 1: 3: 36 *i*-PrNH₂-MeOH-CHCl₃) to give 4-methoxybenzylamine (107 mg, 98%) as a colorless oil.

Method D: To a stirred solution of *N*-(4-methoxybenzyl)-2,4-dinitrobenzenesulfonamide (294 mg, 0.80 mmol) in DMF (2 mL), PhSH (176 mg, 1.60 mmol, 2 equiv) was added. After stirring 15 min at room temperature, the reaction mixture was directly chromatographed on silica gel (8% MeOH-CHCl₃ and then 1: 3: 36 *i*-PrNH₂-MeOH-CHCl₃) to give 4-methoxybenzylamine (100 mg, 91%) as a colorless oil.

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References and Notes

- (1) Fukuyama, T.; Jow, C.-K.; Cheung, M. *Tetrahedron Lett.* **1995**, *36*, 6373.
- (2) For 2-nitrobenzenesulfonamides, see: (a) An, H.; Cook, P. D. *Tetrahedron Lett.* **1996**, *37*, 7233. (b) Yang, L.; Chiu, K. *Tetrahedron Lett.* **1997**, *38*, 7307. (c) Swayze, E. E. *Tetrahedron Lett.* **1997**, *38*, 8643. (d) Miller, S. C.; Scanlan, T. S. *J. Am. Chem. Soc.* **1997**, *119*, 2301. (e) An, H.;

- Cummins, L. L.; Griffy, R. H.; Bharadwaj, R.; Haly, B. D.; Fraser, A. S.; Wilson-Lingardo, L.; Risen, L. M.; Wyatt, J. R.; Cook, P. D. *J. Am. Chem. Soc.* **1997**, *119*, 3696. (f) An, H.; Haly, B. D.; Fraser, A. S.; Guinosso, C. J.; Cook, P. D. *J. Org. Chem.* **1997**, *62*, 5156. (g) Wang, T. M.; An, H. Y.; Vickers, T. A.; Bharadwaj, R.; Cook, P. D. *Tetrahedron* **1998**, *54*, 7955. (h) Reichwein, J. F.; Liskamp, R. M. J. *Tetrahedron Lett.* **1998**, *39*, 1243. (i) Mohamed, N.; Bhatt, U.; Just, G. *Tetrahedron Lett.* **1998**, *39*, 8213. (j) Hidai, Y.; Kan, T.; Fukuyama, T. *Tetrahedron Lett.* **1999**, *40*, 4711. (k) Kung, P.-P.; Swayze, E. *Tetrahedron Lett.* **1999**, *40*, 5651. (l) Turner, J. J.; Wilschut, N.; Overkleeft, H. S.; Klaffke, W.; van der Marel, G. A.; van Boom, J. H. *Tetrahedron Lett.* **1999**, *40*, 7039. (m) Lin, X.; Dorr, H.; Nuss, J. M. *Tetrahedron Lett.* **2000**, *41*, 3309. (n) Fujiwara, A.; Kan, T.; Fukuyama, T. *Synlett* **2000**, 1667. (o) Hidai, Y.; Kan, T.; Fukuyama, T. *Chem. Pharm. Bull.* **2000**, *48*, 1570.
- (3) For 4-nitrobenzenesulfonamides, see: (a) Bhatt, U.; Mohamed, N.; Just, G.; Roberts, E. *Tetrahedron Lett.* **1997**, *38*, 3679. (b) Ibuka, T.; Mimura, N.; Aoyama, H.; Akaji, M.; Ohno, H.; Miwa, Y.; Taga, T.; Nakai, K.; Tamamura, H.; Fujii, N.; Yamamoto, Y. *J. Org. Chem.* **1997**, *62*, 999. (c) Wuts, P. G. M.; Northuis, J. M. *Tetrahedron Lett.* **1998**, *39*, 3889.
- (4) (a) Fukuyama, T.; Cheung, M.; Jow, C.-K.; Hidai, Y.; Kan, T. *Tetrahedron Lett.* **1997**, *38*, 5831. (b) Kobayashi, S.; Peng, G.; Fukuyama, T. *Tetrahedron Lett.* **1999**, *40*, 1519. (c) Hone, N. D.; Payne, L. J. *Tetrahedron Lett.* **2000**, *41*, 6149.
- (5) (a) Messeri, T.; Sternbach, D. D.; Tomkinson, N. C. O. *Tetrahedron Lett.* **1998**, *39*, 1669. (b) Messeri, T.; Sternbach, D. D.; Tomkinson, N. C. O. *Tetrahedron Lett.* **1998**, *39*, 1673.
- (6) Strømgaard, K.; Brierley, M. J.; Andersen, K.; Slak, F. A.; Mellor, I. R.; Usherwood, P. N. R.; Krogsgaard-Larsen, P.; Jaroszewski, J. W. *J. Med. Chem.* **1999**, *41*, 5224.
- (7) Fukuyama, T.; Cheung, M.; Kan, T. *Synlett* **1999**, 1301.
- (8) (a) Wipf, P.; Henninger, T. C. *J. Org. Chem.* **1997**, *62*, 1586. (b) Maligres, P. E.; See, M. M.; Askin, D.; Reider, P. J. *Tetrahedron Lett.* **1997**, *38*, 5253. (c) Miller, S. C.; Scanlan, T. S. *J. Am. Chem. Soc.* **1998**, *120*, 2690.

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